## IAP20 Registron 22 DEC 2005

SHIGA7.035APC PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

**Applicant** 

Washio, Y. et al.

Appl. No.

: Unknown

Filed

: Herewith

For

: DEVELOPER COMPOSITION FOR RESISTS AND METHOD

FOR FORMATION OF RESIST

**PATTERN** 

Examiner

Unknown

Group Art Unit

UInknown

## PRELIMINARY AMENDMENT

## Mail Stop Amendment

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 4 of this paper.